Notice of Allowability	Application No.	Applicant(s)	
	10/736,194	HOPPER, PETER J.	
	Examiner	Art Unit	
	Naum B Levin	2825	
	INAUIII D LEVIII	2023	
The MAILING DATE of this communication apperature All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in the or other appropriate communic GHTS. This application is sub-	is application. If not included cation will be mailed in due cours	se. THIS
1. A This communication is responsive to Prelimary Amendment	<u>st12/15/03</u> .		
2. The allowed claim(s) is/are <u>9 and 10</u> .			
3. \square The drawings filed on <u>15 December 2003</u> are accepted by	the Examiner.		
 4. ☐ Acknowledgment is made of a claim for foreign priority unalled all blacks and blacks are sometimed. 1. ☐ Certified copies of the priority documents have 		f).	
Certified copies of the priority documents have		Jo	
Copies of the certified copies of the priority documents have	,		rom the
International Bureau (PCT Rule 17.2(a)).	suments have been received in	i triis riational stage application i	JOHN MIC
* Certified copies not received:			
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Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	of this communication to file a l ENT of this application.	reply complying with the requirer	nents
5. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give	itted. Note the attached EXAMI es reason(s) why the oath or de	NER'S AMENDMENT or NOTICeclaration is deficient.	E OF
6. CORRECTED DRAWINGS (as "replacement sheets") mus	t be submitted.		
(a) ☐ including changes required by the Notice of Draftspers		PTO-948) attached	
1) ☐ hereto or 2) ☐ to Paper No./Mail Date		,	
(b) ☐ including changes required by the attached Examiner's Paper No./Mail Date	s Amendment / Comment or in	the Office action of	
Identifying indicia such as the application number (see 37 CFR 1. each sheet. Replacement sheet(s) should be labeled as such in t) of
7. DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT	sit of BIOLOGICAL MATER FOR THE DEPOSIT OF BIOLO	IAL must be submitted. Note t DGICAL MATERIAL.	he
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Attachment(s) 1. ☑ Notice of References Cited (PTO-892)	E Notice of Inform	mal Datant Application (DTO 45)	2)
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6. ☐ Interview Sum	mal Patent Application (PTO-152	-)
2. Motice of Dranperson's Faterit Drawing Neview (F10-546)		il Date	
3. ☑ Information Disclosure Statements (PTC 1449 or PTO/SB/0 Paper No./Mail Date 2 15 15 15 15 15 15 15		nendment/Comment	
4. Examiner's Comment Regarding Requirement for Deposit	8. 🛛 Examiner's Sta	tement of Reasons for Allowand	:e
of Biological Material	9.	antu Sar	
		VUTHE SIEK PRIMARY EXAMINER	

DETAILED ACTION

This office action is in response to application 10/736,194. Claims 9-10 remain pending in the application.

Allowable Subject Matter

- 1. Claims 9-10 are allowed over prior art of record.
- 2. The following is an examiner's statement of reasons for allowance:

The examiner finds applicant's arguments persuasive.

The prior art of record fails to teach or suggest or render obvious:

A method for reducing variation in parasitic capacitance between the metal lines attributable to a variation in critical dimension corresponding to a width of first and second metal lines, the method comprising the steps of: determining a range of critical dimensions exhibited by a photolithography process, and simulating variation in parasitic capacitance over the critical dimension range by determining the extent of penetration of an overlying third metal line into an inter-line region between the metal lines, a width of the inter-line region determined by a thickness of the conformal middle interlayer dielectric and by the critical dimension, such that penetration of the third metal line elevates parasitic capacitance while reducing parasitic capacitance variation over the critical dimension range.

3. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance".

Art Unit: 2825

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Naum B Levin whose telephone number is 571-272-1898. The examiner can normally be reached on M-F (8:00-4:30).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Matthew S Smith can be reached on 571-272-1907. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

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